

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. 09/026,042
Priority Filing Date February 19, 1998
Inventor Sujit Sharan et al.
Assignee Micron Technology, Inc. and Applied Materials, Inc.
Priority Group Art Unit 1763
Priority Examiner P. Hassanzadeh, Ph.D.
Attorney's Docket No. MI22-1902
Title: RF Powered Plasma Enhanced Chemical Vapor Deposition Reactor and
 Methods of Effecting Plasma Enhanced Chemical Vapor Deposition

PRELIMINARY AMENDMENT

To: Assistant Commissioner for Patents
 Washington, D.C. 20231

From: Frederick M. Fliegel, Ph.D.
 (Tel. 509-624-4276; Fax 509-838-3424)
 Wells, St. John, Roberts, Gregory & Matkin P.S.
 601 W. First Avenue, Suite 1300
 Spokane, WA 99201-3817

Sir:

This is a preliminary amendment accompanying a Request for
 Divisional Application for the above-entitled patent application. Prior to
 examining the application, please enter the following amendments.

AMENDMENTS